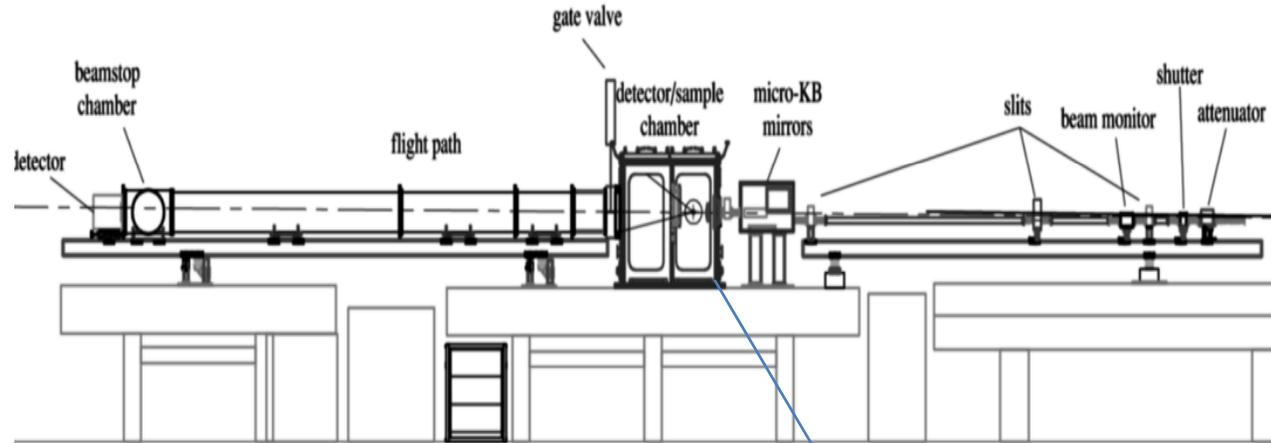


Microbeam SAXS/WAXS, GISAXS and GIXD

X9

- Undulator source, 2.1-20 keV
- Two sets of KB focusing mirrors, <math><10 \mu\text{m}</math> beam size at the sample
- Up to 5 m sample-to-detector distance ($\sim 1 \mu\text{m}^{-1}$ minimum q)
- Simultaneous SAXS/WAXS or GISAXS/GIXD
- Time-resolved measurements



SAXS: Mar CCD at up to 5 m, lowest $q < 0.001 \text{ \AA}^{-1}$
 WAXS: Photonic Science CCD at 0.2 m, highest $q > 2.0 \text{ \AA}^{-1}$

SAXS/WAXS/GISAXS:

Nanometer-scale structures (e.g. block copolymer, lithographical patterns) in bulk and in thin films

GIXD: molecular packing in thin films

